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**(54) SPUTTERING TARGET, AND METHOD FOR MANUFACTURING THE SAME****(57)Abstract:**

**PROBLEM TO BE SOLVED:** To provide a very large sputtering target obtained by butt-welding metal plates of the same quality in which the grain size and the dispersed state of metal crystals and intermetallic compounds are substantially equal between a welded zone and a non-welded zone.

**SOLUTION:** The mean grain size of intermetallic compounds of a welded zone is 60-130% of the mean grain size of intermetallic compounds of a non-welded zone.

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